



International Workshop on Holography and Related Technologies 2017

IWH 2017

First call for paper



November 22 to 24, 2017

Plaza Verde

Numazu City, Shizuoka, Japan

INTRODUCTION

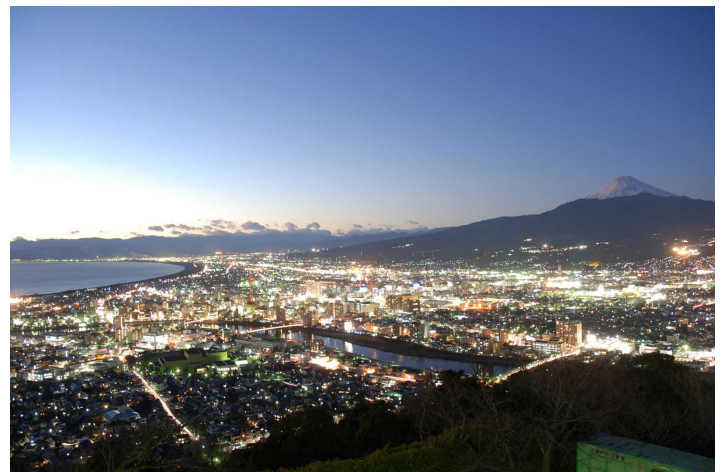
International Workshop on Holography and related technologies (IWH2017) will be held in Plaza Verde, Numazu City, Shizuoka, Japan, from November 22 to 24, 2017. This is the eleventh workshop which covers overall aspects on holography and related technologies, holographic memories, displays, holographic measurement, computer generated holograms and digital holography, ranging from their fundamental physics and technologies to practical systems. The first International Workshop on Holographic Memories (IWHM2007) was held in Penang, Malaysia. IWHM2008, IWHM&D2009-2010 were successfully held in Japan, which includes overall aspects on holographic memories and display. Since 2011, this workshop have extend the scope furthermore, IWH covers the holographic display as well as holographic memory. Last year, IWH2016 was held at Jiaoxi, Yilan, Taiwan with great success. IWH2017 is jointly organized by the following associations in Japan:

- Optical Society of Japan (OSJ)
- International Workshop on Holography
- Center for Optical Research and Education (CORE), Utsunomiya University.
; in corporate with the following societies
- Research Group on Volume Holographic Memory Technology (VHM), OSJ
- Holographic Display Artists and Engineers Club (HODIC), OSJ
- Group of Information Photonics, OSJ
- Digital Optics Research Group, OSJ
- The Institute of Electronics, Information and Communication Engineers
- The Institute of Image and Television Engineers
- Tochigi Optoelectronic Industry Promotion Conference.

SCOPE

All topics related to holography including memories, displays, digital holography, computer generated holography, and holographic optical elements are going to be discussed, ranging from their basic physics and technologies to practical applications, such as materials, components, measurements, basic theory and physics, system design, simulations and devices. In what follows is the list of subject areas, which are not restrictive but suggestive:

1. Holographic Memory
2. Holographic Optical Elements
3. Computer Generated Holography
4. Digital Holography
5. Holographic Display
6. Holography Arts and Design
7. Recording Materials
8. Signal Processing for Holography
9. Devices for Holography
10. Simulation for Holography
11. AR, MR, HUD and HMD with Holography
12. Applications
13. Others



VENUE

Plaza Verde

1-1-4 Otemachi, Numazu City,
Shizuoka, 410-0801, Japan



IWH2017 Website:

<https://www.i-w-holography.org/>

PROGRAM & LANGUAGE

The workshop is composed of a variety of sessions including keynotes, invited talks, contributed papers and poster sessions. From the contributed papers, some of them will be upgraded to the invited talks. Official language of the workshop is English.

SUMMARY PAPER

Authors are cordially invited to contribute papers related to holographic memories, display, digital holography, and related technologies. Summary paper must be written in English and follow these guidelines:

1. Limit the length of the summary paper to 2 (two) pages, including figures, tables, results, discussion, and references.
2. Include the entire summary within a 17 cm. × 22 cm. rectangular area for offset reproduction on A4-size paper.
3. Center the title of the paper at the top of the page. It should be typed in capital bold letters. Below give the names of the authors, and on the next line the affiliation and address. Skip two lines and start the text. The text must be single-spaced. All letters should be no smaller than 11 point.
4. A template is available.
(Download from <https://www.i-w-holography.org/paper-submission/>.)
5. Save the summary paper in Portable Document Format (as a .pdf file).
6. Download "**Submission Form**" from <https://www.i-w-holography.org/paper-submission/> and submit your summary paper attached to this "**Submission Form**" by E-mail to the address below :
iwh17_paper@i-w-holography.org (only for submission)
The deadline for submission is September 29, 2017.
7. Abstracts will be selected on the basis of their originality and the significance of the results. In addition, their importance to the workshop will be considered, and hence review, interpretive, and commentary papers are also welcome.

REGISTRATION

The organizers recommend pre-registration before October 23. Download "**Registration Form**" from <https://www.i-w-holography.org/registration/> and fill out the form and send it by E-mail to the address below :

iwh17_reg@i-w-holography.org (only for registration)

The following registration fees for the IWH2017 are applied.

- | | |
|--|----------|
| ■ Early registration fee before October 23 : | ¥ 35,000 |
| ■ On-site registration fee : | ¥ 45,000 |
| ■ Student : | ¥ 20,000 |

All payments, should be made in **Japanese Yen and only by bank transfer, and are non-refundable. On-site registration should be made with cash in Japanese Yen.** The detail of which will be informed to the pre-registered participants through email.

FURTHER INFORMATION & INQUIRY

Website: <https://www.i-w-holography.org/>
e-mail: iwh2017@i-w-holography.org

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